

PCN #: IO	0303-03 DATE	C: 3/12/2003	MEANS OF DISTI	NGUISHING CH	IANGED DEVICES:
Product Affected:	IDT 79RC32V332-XXX	DH/DHI,	□ Product Mark		
	IDT 79RC32V333-XXX	DH/DHI	□ Back Mark		
Date Effective:	Y step only 4/12/2003		□ Date Code■ Other	Assembly Lo	nt Number
Contact: Bimla				Assembly Le	n number
	raui ct Assurance Manager		Attachment::	Yes	s 🗌 No
	54-6419		Attachment		
	92-8362		Samples:	Available	
	paul@idt.com		Sumples.	Tvanable	
 Die Technology Wafer Fabrication Assembly Process Equipment Material Testing Manufacturing Si Data Sheet Other RELIABILITY/QU This material change Both die attach material	s te VALIFICATION SUMMA e is not expected to adverse	To qualify alterna 79RC32V333 dev This material chan <u>made to the actual</u> ARY: ely affect customer manufactured by A	ice types in PQFP pa nge is not expected to device. s as no changes were ABELSTIK and both	ckage. adversely affect cu made to the actual	for 79RC32V332 and ustomers as no changes were device. nductive die attach material.
IDT records indicate to grant approval or it will be assumed th	NOWLEDGMENT OF F e that you require written n request additional informa hat this change is acceptabl ht to ship either version ma n has been depleted.	otification of this c tion. If IDT does n e.	ot receive acknowled	gement within 30 d	lays of this notice
Customer:		_ □	Approval for	shipments prior	r to effective date.
Name/Date:		E-1	Mail Address:		
Title:		Ph	one#/Fax#:		
CUSTOMER COM	IMENTS:				
IDT ACKNOWLE	DGMENT OF RECEIPT	:			
RECD. BY:			DATE:		



ATTACHMENT 1 - PCN #: I0303-03

PCN Type:	Qualification of alternate ABLESTIK 8361.	J die attach material			
Data Sheet Change	N/A				
Detail of Change	This change affects 79RC32VXXX in "Y st of the date code line. This die attach materia similar size (28 x 28 x 3.5 mm) within the P die attach material below.	al has been previously qualified	l, using a similar package,		
	This change is being implemented to further improve the overall package reliability and manufa yields. The 8361J electrically conductive die attach adhesive is designed for high reliability packaging applications. This high purity adhesive incorporates improvements in epoxy resin and adhesion technology to maintain significant bond strength when exposed to elevated temperatur humidity. This adhesive also exhibits minimal resin bleed and low condensable volatiles. These properties result in greater resistance to delamination and overall improvement in package reliable.				
	Both die attach materials (8390 and 8361J) aconductive die attach material. See attachme	-			
Conversion Schedule	Device Type	Sample Availability	Production Shipment		
	IDT 79RC32V332-XXXDH/DHI	Available	April 14, 2003		

IDT 79RC32V333-XXXDH/DHI Available

April 14, 2003



ATTACHMENT 1 - PCN #: I0303-03

Test Vehicle: IDT79R465

Qualification Test Plan and Results:

Test Description	Test Method	Sample Size/# Of Fails	Test Results (SS/# Of Fails
* Temperature Cycling (-65 °C to 150 °C, 500 cycle)	MIL-STD-883, M 1010	45/0	45/0
* Auto Clave (121 °C, 2 ATM, 168 Hrs)	EIA/JESD22-A102	45/0	45/0
Moisture Sensitivity Classification (Level 3)	JEDEC J-STD-020	11/0	11/0
Internal Visual Inspection	MIL-STD-883, M2010	5/0	5/0
External Visual Inspection	MIL-STD-883, M2009	25/0	25/0
X-ray Examination	Per IDT Specification	45/0	45/0
Bond Pull	MIL-STD-883, M2011	5/0	5/0
Bake & Ball Shear Strength	EIA/JESD22-B116	5/0	5/0
Physical Dimensions	MIL-STD-883, M2016	5/0	5/0
Resistance to Solvents	MIL-STD-883, M2015	3/0	3/0

Notes: * Test requires Moisture Pre-Conditioning sequence.



ATTACHMENT 2 - PCN #: I0303-03

ABLEBOND® 8361J

ELECTRICALLY CONDUCTIVE DIE ATTACH ADHESIVE

PERTIES-	TEST DESCRIPTION	TEST METHOD
(780 Kpsi) PC 2,900 MPa (420 Kpsi) 0°C 120 MPa (18 Kpsi)	Dynamic Tensile Modulus Thermal Analysis on < 0.5 thick specimen	MT-12
0.65%	Dynamic Vapor Sorption after 85°C/85% RH Exposure	PT-65
ROPERTIES-		
2.2 W/mK	Laser Flash	PT-96
	Cu to Cu Joint @ 5x5 mm (200x200mil) area/25 μm bondline thickness	PT-81
	5°C 5,400 MPa (780 Kpsi) °C 2,900 MPa (420 Kpsi) 0°C 120 MPa (18 Kpsi) 0°C 51 MPa (8 Kpsi) 0.65% ROPERTIES- 2.2 W/mK	TEST DESCRIPTION TEST DESCRIPTION 5°C 5,400 MPa (780 Kpsi) Dynamic Tensile Modulus Thermal Analysis on < 0.5 thick specimen °C 2,900 MPa (420 Kpsi) O.5 thick specimen °C 120 MPa (18 Kpsi) O.5 thick specimen 0°C 51 MPa (8 Kpsi) Dynamic Vapor Sorption after 85°C/85% RH Exposure ROPERTIES- Laser Flash 0.02 ohm/cm ² Cu to Cu Joint @ 5x5 mm (200x200mil) area/25 µm bondline thickness

The figures shown above are typical values only. If you need to write a specification, please request our current Standard Relese Specification.



ATTACHMENT 2 - PCN #: I0303-03

Ablebond[®] 8361J

MECHANICAL PROPERTIES- POST CURE Die Shear Strength @ 25°C 17 kg/die			TEST DESCRIPTION	TEST METHOD
			2x2 mm Si Die on Ag/Cu LF (80x80 mil)	MT-4
Die Shea @.25°C	r Strength vs. 7 @ 200°C	Temperature (kg _r /die) @ 250°C	3x3 mm (120x120 mil) Si Die Substrate	MT-4
31	2.6	2.2	Ag/Cu Leadframe	
29	3.7	3.6	Bare Cu Leadframe	
31	2.1	1.6	Pd/Ni/Cu Leadframe	Section (L., 1
	r Strength After for 168 Hours	r 85°C/85% RH (kg./die)	3x3 mm (120x120 mil) Si Die	MT-4
@25°C	@200°C		Substrate	
25	1.7		Ag/Cu Leadframe	
24	2.5		Bare Cu Leadframe	State and the second second
27	1.7	·	Pd/Ni/Cu Leadframe	Trans Decor
Chip Wa	rpage @ 25°C v	s. Chip Size	0.38 mm (15 mil) thick Si Die	MT-15
Chip Size		Warpage	0.2 mm (8 mil) thick Ag/Cu	and the second
7.6x7.6 m	m (300 x 300 m	nil) 8 µm	Leadframe	and the set of the
10.2x10.2	mm (400 x 400) mil) 18 µm		
12.7x12.7	mm (500 x 500) mil) 33 µm		
Chip Wa	rpage vs. Post	Cure Thermal Process	12.7 x 12.7 x 0.38 mm Si Die	MT-15
			(500 x 500 x 15 mil)	
			on 0.2 mm (8 mil) Thick Leadframe	
Post Cure	+ Wirebond	+ Post Mold Bake	Substrate	
	(1 min @ 250°C)	(4 hrs @ 175°C)		
32 µm	36 µm	38 µm	Ag/Cu Leadframe	
34 µm	36 µm	39 µm	Bare Cu Leadframe	

The figures shown above are typical values only. If you need to write a specification, please request our current Standard Relese Specification.



ATTACHMENT 2 - PCN #: I0303-03

ABLEBOND® 8390

SNAP CURE DIE ATTACH ADHESIVE

PHYSIOCH POST CURE	EMICAL PROPI	ERTIES -	TEST DESCRIPTION	TEST METHOD	
Ionics	Chloride	1 ppm	1000	Teflon flask	CT-13
	Sodium	2 ppm	3.1.	5 gm sample/ 20-40 mesh	T-4
	Potassium	None Detected	-	50 gm DI water 100°C for 24 hours	
Water Extra	ct Conductivity	18 µmhos/cm	Section		CT-6
pН		6.2		5. Min. 19	CT-7
Weight Loss	@ 300°C	0.6%	11.20	Thermogravimetric Analysis	PT-20
Glass Transi	tion Temperature	73°C	A. (Sa	TMA Penetration Mode	MT-14
Coofficients	f Theorem al Error		4.200	TRAA Ferrarelan Made	МТ-9
Coefficient o	of Thermal Expan Below Tg	60 ppm/°C		TMA Expansion Mode	W11-9
	Above Tg	135 ppm/°C		A Construction of the second se	
	Above 1g	135 ppm/ C			1
Dynamic Te	nsile Modulus			Dynamic Mechanical Thermal	MT-12
Alexandre dans	@ -65°C	6,330 MPa		Analysis using <0.5mm thick	1.2.5
		(920 Kpsi)		specimen	
	@ 25°C	4,650 MPa		CONTRACT IN 265	1
		(675 Kpsi)			
	@ 150°C	1,390 MPa		94	
		(200 Kpsi)			1.
	@ 250°C	517 MPa		1 - 1 - 1 1a, 7250 CL	
		(75 Kpsi)		and the strength of 2000	1
Moisture Absorption 1.1%				Dynamic Vapor Sorption	PT-65
@ Saturation			after 85°C/85% RH exposure		
THERMAL POST CURI	ELECTRICAL	PROPERTIES -		TEST DESCRIPTION	TEST METHOD
Thermal conductivity 1.8 W/m°K @ 121°C		<i>k</i> .	C-MATIC Conductance Tester	PT-40	
Volume resistivity 0.0003 ohm-cm			4-Point Probe	PT-46	

The figures shown above are typical values only. If you need to write a specification, please request our current Standard Release Specification.



ATTACHMENT 2 - PCN #: I0303-03

ABLEBOND® 8390

MECHANICAL PROPERTIES - POST CURE				TEST DESCRIPTION	TEST METHOD	
Die Shear Strength @ 25°C 11 kg/die				lie	2x2mm Si die on Ag/Cu LF (80x80 mil)	MT-4
Die Shear Strength (kg/die) vs. Temperature <u>Snap Cured</u> <u>Oven Cured</u>				erature	3x3mm (120x120 mil) Si die on	MT-4
@25°C				@250°C	Substrate	
20	2.4 1.2	24	4.8	3.1	Ag/Cu leadframe	
13	3.0 2.7	-	-	-	Bare Cu leadframe	
18	3.5 1.8	• 10 m			Pd/Ni/Cu leadframe	1 5 2 cs
Die Shear Strength (kg/die) after 85°C/85% RH exposure for 168 hours			C/85% RH	3x3 mm Si die on Ag/Cu LF	MT-4	
	Cured	Oven (Cured		an wild dispetitle the period of	化二乙酰 化合物
	@200°C		@200°C		<u>Substrate</u>	her example and
17	1.0	14	3.0		Ag/Cu leadframe	rignistica
10	1.1	-			Bare Cu leadframe	
18	1.3	de la compete	A start -		Pd/Ni/Cu leadframe	
Chip	Warpage (µm)	@ 25°C	vs. Chip	Size	0.38mm (15mil) thick Si die on 0.2mm thick Ag/Cu leadframe	MT-15
Snap (Cured	Oven Ci	ured		Chip Size	an an an ang ta
11		22			7.6 x 7.6mm (300x300mil)	
29		44			10.2 x 10.2mm (400x400mil)	2 · · · ·
52		68			12.7 x 12.7mm (500x500mil)	
Chip Warpage (µm) vs. Post Cure Thermal Process		7.6 x 7.6 x 0.38mm Si die (300 x 300 x 15 mil) on 0.2mm (8 mil) thick LF	MT-15			
Snap	Cured				providence, the adjustice show	al water of
Ag/Cu		Cu LF			<u>Condition</u>	
11	8				Post Cure	
13	16				+Wirebond (1 min.@250°C)	
13	20				+Post Mold Bake (4 hours @ 175°C)	

The figures shown above are typical values only. If you need to write a specification, please request our current Standard Release Specification.